

Consideration of Synchrotron Radiation Ablation Mechanism

Hidejiro Miki, Sou Lin*, Tomoji Kawai*, Muneo Sasaki**,
Katsumi Hanamoto, Shigeru Imai and Yasuyuki Nakayama

Abstract

Various oxide thin films and functional carbon compound thin films were prepared by the synchrotron radiation ablation method. The deposition rate of these thin films was investigated. The mechanism involved in the synchrotron radiation ablation was considered. It is clarified that the carbon compound with the sp^3 -hybridized structure is easily ablated but the carbon compound with the sp^2 -hybridized structure is unable to be ablated.

Faculty of Science and Engineering, Ritsumeikan University, 1-1-1 Noji-Higashi,
Kusatsu, 525-8577, Japan

*The Institute of Science and Industrial Research, Osaka University, 8-1 Mihogaoka,
Ibaraki, Osaka 567-0047 Japan

**The Industrial Research Center of Shiga Prefecture, 232 Kamitoyama, Ritto-tyo,
Kurita-gun, Shiga 520-3004, Japan